



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:)
)
Ryoichi INANAMI et al.)
)
Serial No.: Not yet assigned) Group Art Unit: Not assigned
)
Filed: July 26, 2001) Examiner: Not assigned

For: METHOD AND SYSTEM FOR PRODUCING SEMICONDUCTOR DEVICES

Assistant Commissioner for Patents
Washington, DC 20231

Sir:

INFORMATION DISCLOSURE STATEMENT UNDER 37 C.F.R. § 1.97(b)

Pursuant to 37 C.F.R. §§ 1.56 and 1.97(b), applicants bring to the Examiner's attention the documents listed on attached Form PTO-1449. Copies of the listed documents are attached. Applicants respectfully request that the Examiner consider the documents listed on attached Form PTO-1449 and indicate that they were considered by making an appropriate notation on this form.

This Information Disclosure Statement is being filed with the above-referenced application.

This submission does not represent that a search has been made or that no better art exists and does not constitute an admission that the listed documents are material or constitute "prior art." If the Examiner applies the documents as prior art against any claim in the application and applicants determine that the cited documents do not constitute "prior art" under United States law, applicants reserve the right to present to the office the relevant facts and law regarding the appropriate status of such documents.

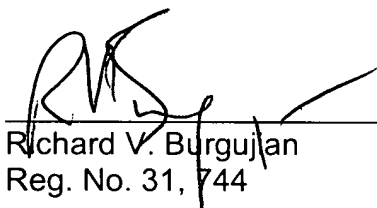
Applicants further reserve the right to take appropriate action to establish the patentability of the disclosed invention over the listed documents, should they be applied against the claims of the present application.

If there is any fee due in connection with the filing of this Statement, please charge the fee to our Deposit Account No. 06-0916.

Respectfully submitted,

FINNEGAN, HENDERSON, FARABOW,
GARRETT & DUNNER, L.L.P.

By:


Richard V. Burgujan
Reg. No. 31, 744

Dated: July 26, 2001

Enclosures
RVB/FPD/dvz

INFORMATION DISCLOSURE CITATION
(Use several sheets if necessary)

Jc971 U.S. PTO

09/912398

07/26/01

Atty. Docket No. 04329.2012				Serial No. Not Yet Assigned			
Applicant Ryoichi INANAMI et al.							
Filing Date July 26, 2001				Group			
U.S. PATENT DOCUMENTS							
Examiner Initial*		Document Number	Date	Name	Class	Sub Class	Filing Date If Appropriate
FOREIGN PATENT DOCUMENTS							
		Document Number	Date	Country	Class	Sub Class	Translation Yes or No
OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)							
		Inanami, R. et al., " Throughput Enhancem ent Strategy of Maskless Electron Beam Direct Writing for Logic Device", IEEE-2000 Technical Digest pp.833-836, Decem ber 10-13, 2000.					
		Inanami, R. et al., "Exposure Pattern Data Generation Apparatus Associated with Standard Cell Library and Charged Beam Exposure", U.S. Serial No. 09/817,270, f iled March 27, 2001.					
Examiner				Date Considered			
*Examiner: Initial if reference considered, whether or not citation is in conf ormance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.							
Form PTO 1449				Patent and Trademark Office - U.S. Department of Commerce			